## APPLICATION NO. 10/035346

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## **CLMPTO**

1. (Currently Amended) A varactor comprising:
a diode junction;
a depletion region adjacent to the diode junction; and
a doped region beginning at the diode junction, including the
depletion region and having a nonuniform dopant concentration profile that
continuously increases with increasing depth of the doped region starting from the
diode junction and continuing to a peak concentration region at the deepest

portion of the doped region;
and wherein the continuously increasing nonuniform dopant concentration profile causes the varactor to have an approximately linear capacitance/voltage response characteristic.

- Canceled
- 3. (Previously Amended) A varactor as defined in claim 1 wherein: the nonuniform depart concentration profile is defined by an equation N=Bxexp(m), where N is the depart concentration, x is the depth of the depend region, B is a concentration constant and m is an exponent that determines the degree of curvature of the depart profile, and m is greater than 1.
  - 4. Canceled
  - 5. (Original) A varactor as defined in claim 3 wherein m is about 3.
  - (Previously Amended) A varactor as defined in claim 3 wherein:
     B is in a range from about 1.0E13/cm3 to about 1.0E19/cm3; and m is greater than one.
- 7. (Original) A varactor as defined in claim 6 wherein 8 is about 1.0E16/cm3.
  - 8.-10. Canceled

CLAIMS 11-17 (CANCELLED)